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**First Semester M.Tech. Degree Examination, Dec.2015/Jan.2016**  
**Digital VLSI Design**

Time: 3 hrs.

Max. Marks:100

**Note: Answer any FIVE full questions.**

1.
  - a. Derive the expression for threshold voltage  $V_T$  in terms of body effect and surface potential. **(10 Marks)**
  - b. Calculate the threshold voltage,  $V_{TO}$  at  $V_{SB} = 0$  V, for a polysilicon gate n-channel MOS transistor, with the following parameters: Substrate doping density,  $N_A = 10^{16} \text{ cm}^{-3}$ , Polysilicon gate density (doping),  $N_D = 2 \times 10^{20} \text{ cm}^{-3}$ , gate oxide thickness  $t_{OX} = 400 \text{ \AA}$ , oxide interface fixed charge density,  $N_{OX} = 4 \times 10^{10} \text{ cm}^{-2}$  and assume  $\phi_{F(\text{gate})} = 0.55$  V,  $\epsilon_{si}$ , the silicon permittivity as  $11.7 \times 8.85 \times 10^{-14} \text{ F/cm}$  and  $\epsilon_{OX}$ , Permittivity of gate oxide in  $3.97 \times 8.85 \times 10^{-14} \text{ F/cm}$ . **(06 Marks)**
  - c. Why we need scaling and what are its effects in long channel and short channel? **(04 Marks)**
2.
  - a. Derive expression for  $V_{OH}$ ,  $V_{OL}$ ,  $V_{IL}$  and  $V_{IH}$  in terms of threshold voltage, for n-type depletion mode load inverter. **(10 Marks)**
  - b. Calculate the critical voltages  $V_{OL}$ ,  $V_{OH}$ ,  $V_{IL}$  and  $V_{IH}$  and find the noise margins of the depletion load inverter circuit with the following parameters:  $V_{DD} = 5$  V,  $V_{TO(\text{driver})} = 1.0$  V,  $V_{TO(\text{load})} = -3.0$  V,  $\left(\frac{W}{L}\right)_{(\text{driver})} = 2$ ,  $\left(\frac{W}{L}\right)_{(\text{load})} = \frac{1}{3}$ ,  $K_{n(\text{driver})} = K_{n(\text{load})} = 25 \frac{\mu\text{A}}{\text{V}^2}$ ,  $\gamma = (0.4) \text{ V}^{\frac{1}{2}}$ ,  $\phi_F = -0.3$  V. Assume suitable values for iterations. **(08 Marks)**
  - c. Differentiate enhancement mode and depletion mode inverters. **(02 Marks)**
3.
  - a. Obtain expression for  $\tau_{PHL}$  and  $\tau_{PLH}$  for CMOS inverter in terms of  $V_T$  and  $V_{DD}$  and capacitance. **(10 Marks)**
  - b. With suitable circuit explain, how to estimate interconnect Parasitics. **(05 Marks)**
  - c. Show that switching power dissipation of CMOS inverter is given by  $P_{avg} = C_{load} V_{dd}^2 \cdot f$ , where  $f$  is the switching frequency. **(05 Marks)**
4.
  - a. Explain briefly with suitable circuit pass transistor in dynamic logic design. **(05 Marks)**
  - b. Explain how to overcome threshold voltage drop in integrated circuits using voltage bootstrapping technique. **(10 Marks)**
  - c. Briefly explain cascaded domino CMOS logic circuit for high performance dynamic logic circuit. **(05 Marks)**
5.
  - a. Explain memory structure of SRAM with read and write circuitry with the help of read and write timing diagrams. **(10 Marks)**
  - b. Explain briefly Flash-memory using NOR-cell configuration. **(06 Marks)**
  - c. Differentiate DRAM and SRAM. **(04 Marks)**
6.
  - a. What is leakage power dissipation? On what parameters does it depend? **(04 Marks)**
  - b. Explain briefly adiabatic logic circuit with AND / NAND logic gates. **(10 Marks)**
  - c. Explain the concept of switching activity with suitable state transition diagram. **(06 Marks)**

Important Note : 1. On completing your answers, compulsorily draw diagonal cross lines on the remaining blank pages.  
 2. Any revealing of identification, appeal to evaluator and/or equations written eg. 42+8 = 50, will be treated as malpractice.

- 7 a. Differentiate BJT, CMOS and BiCMOS. (06 Marks)  
b. Explain the static behavior of BiCMOS inverter. (10 Marks)  
c. Realise basic NAND gate with  $V_A$  and  $V_B$  as inputs by using BiCMOS. (04 Marks)
- 8 Write a short notes on the following:  
a. ESD-Protection in I/O circuits.  
b. Switching delay in BiCMOS logic circuits.  
c. Parametric yield estimation in design for manufacturability.  
d. Worst case analysis in manufacturing process. (20 Marks)

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